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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/577,209	05/23/2000	Arnoldo Valenzuela	B0843-991160	4200
26379	<b>7590</b> 12/13/2005		EXAMINER	
DLA PIPER RUDNICK GRAY CARY US, LLP			SHAFER, RICKY D	
	ERSITY AVENUE LTO, CA 94303-2248		ART UNIT	PAPER NUMBER
	,		2872	
			DATE MAILED: 12/13/2005	

Please find below and/or attached an Office communication concerning this application or proceeding.

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:	Application No.	Applicant(s)	— <i>J</i>			
	09/577,209	VALENZUELA ET AL.				
Office Action Summary	Examiner	Art Unit				
	Ricky D. Shafer	2872				
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the o	correspondence address				
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.  - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.  - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.  - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133).  Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).						
Status						
Responsive to communication(s) filed on <u>04 Notes</u> This action is <b>FINAL</b> . 2b) ☑ This      Since this application is in condition for alloware closed in accordance with the practice under E	action is non-final.  nce except for formal matters, pre-		is			
Disposition of Claims						
4) ⊠ Claim(s) 1-13 and 31-37 is/are pending in the a 4a) Of the above claim(s) is/are withdray 5) □ Claim(s) is/are allowed. 6) ⊠ Claim(s) 1-13 and 31-37 is/are rejected. 7) □ Claim(s) is/are objected to. 8) □ Claim(s) are subject to restriction and/or	vn from consideration.					
Application Papers						
9) The specification is objected to by the Examine 10) The drawing(s) filed on is/are: a) acce Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the Ex	epted or b) objected to by the drawing(s) be held in abeyance. Se ion is required if the drawing(s) is ob	e 37 CFR 1.85(a). njected to. See 37 CFR 1.121				
Priority under 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).  a) All b) Some * c) None of:  1. Certified copies of the priority documents have been received.  2. Certified copies of the priority documents have been received in Application No  3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).  * See the attached detailed Office action for a list of the certified copies not received.						
Attachment(s)  1) Notice of References Cited (PTO-892)  2) Notice of Draftsperson's Patent Drawing Review (PTO-948)  3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date	4) Interview Summan Paper No(s)/Mail D 5) Notice of Informal 6) Other:					

## **DETAILED ACTION**

- 1. A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 11/04/2005 has been entered.
- 2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 3. Claims 1, 3-6, 8-13, 31, 33, 34, 36 and 37 are rejected under 35 U.S.C. 103(a) as being unpatentable over Korte in view of Pichel ('533) or Jochim ('469).

Korte discloses a method of manufacturing a telescope mirror comprising the steps of: (a) providing a mandrel defining the geometry of the telescope mirror, (b) depositing a reflective layer (silver or gold) on the mandrel surface, (c) electroforming a mirror body (nickel, chromium, copper or an alloy thereof) onto the reflective layer by an electrochemical process, (d) releasing the mirror body with the reflective layer from the mandrel, wherein the mirror body and reflective layer forms a self-supported telescope mirror due to the fact that the mirror has a thickness between 5 and 12 mm and wherein the mandrel comprises glass, note page 1442, column 1, line 52 to page 1442, column 2, expect for explicitly stating that the electroforming process and the release process are controlled such that the building up of internal mechanical tension within the mirror body is suppressed.

Pichel and Jochim each teach it is well known to use necessary controls (see column 4, lines 4-21 and column 3, line 73 to column 4, line 12, respectively) in the same field of endeavor for the purpose obtaining a stress free mirror.

Therefore, it would have been obvious to one of ordinary skill in the art at the time the invention was made to modify the electroforming process and the release process of Korte to include necessary controls commonly used and employed in the art, as taught Pichel or Jochim, in order to obtain a stress-free mirror without internal mechanical tension.

As to the limitations of claim 3, Pichel and Jochim each teach it is well known to clean a surface of a mandrel (see column 2, lines 67-71 and column 3, lines 64-71 and column 2, lines 67-72 and column 3, lines 60-66, respectively) in the same field of endeavor before depositing a layer onto the surface of said mandrel.

Therefore, it would have been obvious to one of ordinary skill in the art at the time the invention was made to modify the mandrel of Korte to be clean before depositing the reflective layer, as taught Pichel or Jochim, in order to reduce surface imperfections and/or improve the adhesion strength.

As to the limitations of claim 5, it is well known and would have obvious to one of ordinary skill in the art at the time the invention was made to manufacture optic elements in a clean work environment for the purpose of preventing dust and impurities from affecting the overall optical properties of the finally produced optical elements.

As to the limitations of claims 8-11, it is well known and would have been obvious to one of ordinary skill in the art at the time the invention was made to attach a mirror body to a supporting structure either before or after releasing a mirror body from a mandrel for the purpose

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reinforcing and/or increasing the rigidity of the mirror body before the mirror body is removed from the mandrel or mounting the mirror body to a mounting (supporting) structure of a telescope.

4. Claims 2, 32 and 35 are rejected under 35 U.S.C. 103(a) as being unpatentable over Korte in view of Pichel ('533) or Jochim ('469) as applied to claims 1, 3-6, 8-13, 31, 33, 34, 36 and 37 above and further in view of George et al ('944) or Vaaler ('376).

Korte in view of Pichel or Jochim discloses all of the subject matter claimed, note the above explanation, except for explicitly stating that the an internal mechanical tension is measured during the electroforming process using an additional electroforming sample which is electroformed in parallel or an electronic stress measurement device.

George et al and Vaaler each teach it is well known to use a stress measurement device in the same field of endeavor for the purpose monitoring and controlling the internal stress produced during the electroforming process.

Therefore, it would have been obvious to one of ordinary skill in the art at the time the invention was made to modify the electroforming apparatus of Korte in view of Pichel or Jochim to include a stress measurement device, as taught by George et al or Vaaler, in order to monitor and control the internal stress produced during the electroforming process so as to obtain an uniform stress free deposition.

5. Claim 7 is rejected under 35 U.S.C. 103(a) as being unpatentable over Korte in view of Pichel ('533) or Jochim ('469) as applied to claims 1, 3-6, 8-13, 31, 33, 34, 36 and 37 above, and further in view of Engelhaupt et al ('611).

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Korte in view of Pichel or Jochim discloses all of the subject matter claimed, note the above explanation, except for explicitly stating that the electroforming step is carried out using an electrochemical liquid having a temperature between 40 degrees Celsius and 70 degrees Celsius.

Engelhaupt et al teaches it is known to use an electrochemical liquid having a bath temperature between 40 degrees Celsius and 70 degrees Celsius in the same field of endeavor for the purpose controlling the internal stress produced during the electroforming process.

Therefore, it would have been obvious to one of ordinary skill in the art at the time the invention was made to modify the bath of the electroforming apparatus of Korte in view of Pichel or Jochim to include a temperature between 40 degrees Celsius and 70 degrees Celsius, as taught by Engelhaupt et al, in order to control the internal stress produced during the electroforming process so as to obtain an uniform stress free deposition.

6. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Ricky D. Shafer whose telephone number is (571) 272-2320. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300. Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

RDS

December 08, 2005